

## 感光型線路油墨滾塗阻劑(LP-460 RF8) Liquid Photo-imaginable Roller-Coating Resistor

LP-460 RF8 系列為一種接觸曝光鹼液顯影型之線路光阻劑，為一性能優異的滾塗型印刷油墨，顯影後忠於底片具有高度之解像力。此光阻劑具有快速乾燥及良好的印刷平整性，無曝光變色性，曝光顯影後其表面堅硬可抗電鍍，耐鍍銅、鍍錫鉛及純錫。亦可用於耐酸鹼性蝕刻，適用於精密線路之製造。

LP-460 RF8 series is a roller-coating contact exposure type photo-imaginable plating resist designed for printed circuit fabrication. It has sharp pattern, high resolution and excellent properties with fine line defined. Also has fast curing speed, excellent coating properties and forming a tough protective film after curing, withstanding iron ( II ) chloride solution, copper ( II ) chloride solution etching, and plating resist. This film is easily stripped by caustic soda solution.

### 技術資料 Technical Data

項目	LP-460 RF8
顏色 Color	藍色 blue
黏度(25°C)	10± 1PS (VT-04, #1 針, #1 Spindle)
預烤條件 preheat Condition	熱乾燥 75±5 °C 約 10±2 分鐘 heating at 75±5 °C about 10±2 minutes
曝光條件 UV Exposure	200~250 mJ/cm <sup>2</sup>
鉛筆硬化(JIS K5400) Film hardness by pencil lead	≥ 2H
抗酸/鹼蝕刻 Acid/Base etching resistance	良好 Excellent
抗電鍍 Plating resistance	良好 Excellent
顯影條件 Imaging conditions	30~35 秒在 30±2 °C 的 1~1.1%碳酸鈉水溶液，水壓 1.5~2.0 30-35 seconds at 30±2°C for 1-1.1 % Na <sub>2</sub> CO <sub>3</sub> aqueous solution
去墨條件 Condition of remove coating film by alkali	20 ±5 秒在 50±5 °C 的 5±1 % NaOH 水溶液 20 ±5 seconds at 50±5°C for 5±1 % NaOH aqueous solution
貯存安定性 Shelf life at 20-30 °C under dark packing	6 個月 6 month

上各項數據僅供參考 The above information is for reference only.